

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

11675.76

Application Number

09/627.649

Applicant(s)

Sandhu, et al.

Filing Date

July 28, 2000

Group Art Unit

2811

2814

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	CLASS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Th	A	5,445,996	8/95	Kodera et al.	438	633	
Th	B	5,486,493	1/96	Jeng	438	623	
Th	C	5,399,235	3/95	Mutsaers et al.	438	633	
Th	D	5,420,075	5/95	Homma et al.	438	624	
Th	E	5,599,740	2/97	Jang et al.	438	626	
Th	F	5,677,239	10/97	Isobe	438	633	
Th	G	5,795,829	8/98	Shen	438	694	
Th	H	5,708,303	1/98	Jeng	257	758	

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Th		M.K. Jain et al., "Advanced Metalization and Interconnect Systems for ULSI Applications: Homogenous and Multilayer Low-K Interlevel Dielectric Architectures for Capacitance Reduction," Conference at University of California, Berkeley, California, October 1996.
Th		Tetsuya Homma, "Fluorinated SiO2 Films for Interlayer Dielectrics in Quarter-Micron ULSI Multilevel Interconnections," Mat Res Soc Symp Proc Vol 381, pp 239-248, 1995.

EXAMINER

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DATE CONSIDERED

2/28/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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J. Wary et al., "Vacuum-Deposited Parylene AF-4: A Thermally Stable, Low Dielectric Constant Polymer For Interlayer Dielectric Use," DUMIC Conference, pp. 207-213, February, 1996.



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EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TU	1.	6,146,987	11/2000	Wang, et al.	438	618	
TU	2.	6,177,286	1/2001	Chiddambarrao, et al.	438	14	

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

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Docket Number (Optional) 11675.76.3	Application Number 09/627,649
Applicant(s) Sandhu, et al	
Filing Date July 28, 2000	Group Art Unit 2844

U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

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OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

APPENDIX

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